

**EV372453882**

Inventor: **H. Daniel Dulman et al.**  
Title: **Methods of Printing Structures**  
Assignee: **Micron Technology, Inc.**  
Serial No.: **Filed Herewith**  
Filing Date: **Filed Herewith**

**INFORMATION DISCLOSURE STATEMENT**

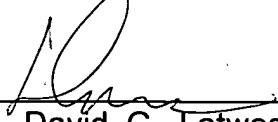
**PURSUANT TO 37 C.F.R. §§1.56, 1.97 AND 1.98**

In compliance with 37 C.F.R. §§1.56, 1.97 and 1.98, your attention is directed to the references listed on the attached Form PTO-1449.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a divisional of co-pending application Serial No. 10/226,005, filed August 21, 2002. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. §1.98(d) and MPEP §609(2). No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 3/24/04 Attorney:   
David G. Latwesen, Ph.D.  
Reg. No. 38,533  
WELLS, ST. JOHN P.S.

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2513		SERIAL NO. Filed Herewith	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT H. Daniel Dulman et al.			
				FILING DATE Filed Herewith		GROUP Unknown	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	5,308,721	05/94	Garofalo et al.			
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes      No
	AM						
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AR	Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method",					
		19th Annual BACUS Sympos. on Photomask Technology, Monterey, CA, 9/99, SPIE Vol. 3873 (1999), pp. 288-296.					
	AS	Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method					
		(II)", 20th Annual BACUS Sympos. on Photomask Technology, Proceedings of SPIE Vol. 4186 (2001), pp.801-809.					
	AT						
EXAMINER				DATE CONSIDERED			
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>							